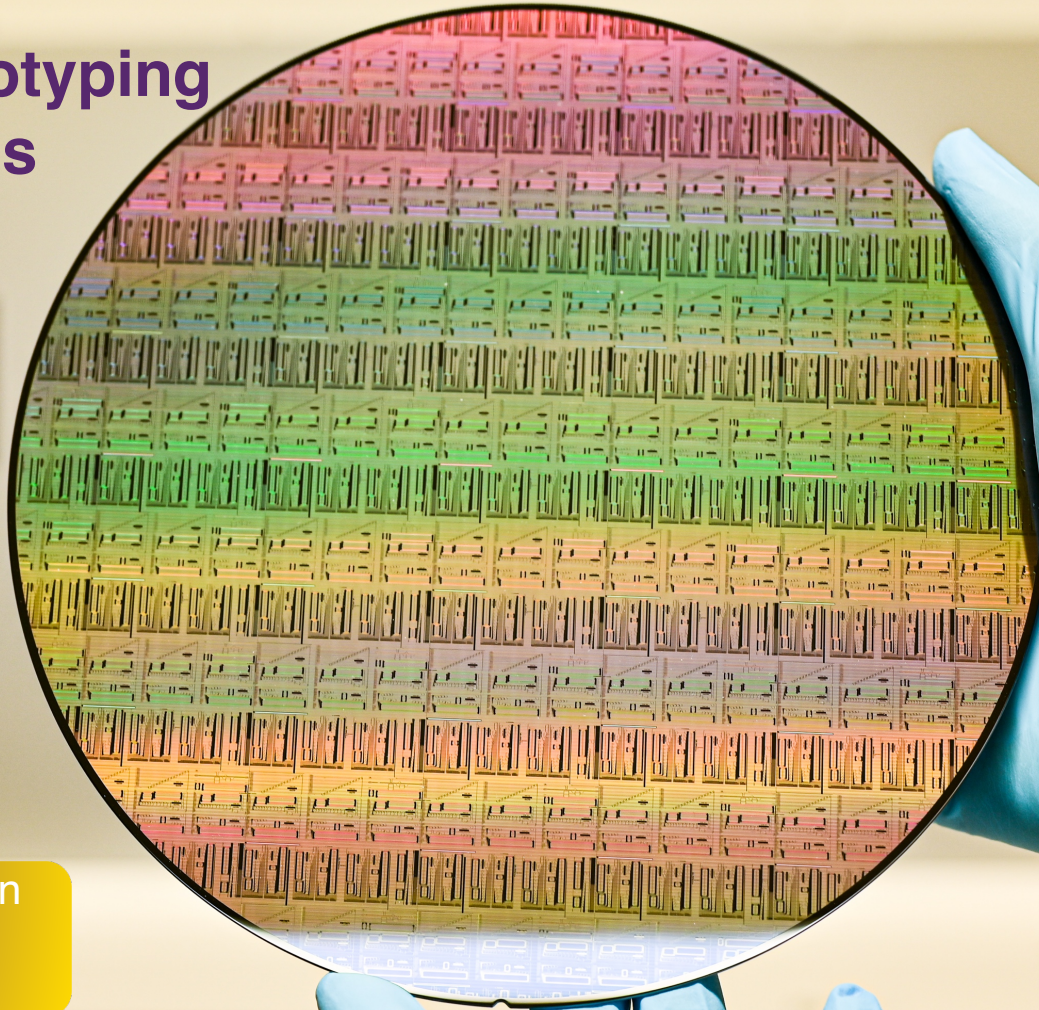


Low loss PICs: From fast prototyping to high volumes



Dr. Michael Geiselmann

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LIGENTEC

Leader in low loss Silicon Nitride Integrated Photonics



EPFL



LIGENTEC

European PIC Company

European origin

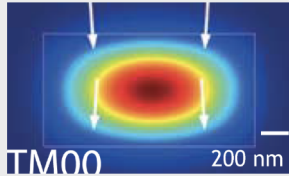
Europe based



Headquarters in Lausanne (CH)

Originating from EPFL (Kippenberg Lab)

Thick SiN – the game changer



90% of the light is confined

- Low propagation loss
- Small chip size
- Non-linear optics
- High Power, VIS to IR

All Nitride Core Technology: combining the benefits of

- **Silicon Nitride** (VIS-IR, low loss, high power) with
- **Silicon Photonics** (small chip size, scalability)

Versatile PIC Platform

3+ thicknesses	10 process modules	Extensive PDK																						
800 nm		<table border="1"> <tr> <td>Design rules</td> <td>Components</td> <td rowspan="5"> Design flows </td> </tr> <tr> <td>Design Rule Checks</td> <td> <ul style="list-style-type: none"> • Waveguides, delay lines • Couplers / MMIs • Crossings • Filters (RRs, AWGs) • Switches </td> </tr> <tr> <td>Layout files</td> <td> <ul style="list-style-type: none"> • Polarization mgt </td> </tr> <tr> <td>Primitives</td> <td>Optical I/O</td> </tr> <tr> <td>Building Blocks</td> <td> <ul style="list-style-type: none"> • Grating couplers • Inverted tapers • Spot size converters </td> </tr> <tr> <td>400 nm</td> <td> </td> <td rowspan="5"> Simulations <ul style="list-style-type: none"> • Component and circuit simulation • Technology files • Cross section </td> </tr> <tr> <td>150 nm</td> <td> </td> </tr> <tr> <td>custom</td> <td> <ul style="list-style-type: none"> ○ Modular ○ CMOS compatible ○ Scalable </td> </tr> <tr> <td></td> <td> </td> </tr> <tr> <td></td> <td> </td> </tr> </table>	Design rules	Components	Design flows 	Design Rule Checks	<ul style="list-style-type: none"> • Waveguides, delay lines • Couplers / MMIs • Crossings • Filters (RRs, AWGs) • Switches 	Layout files	<ul style="list-style-type: none"> • Polarization mgt 	Primitives	Optical I/O	Building Blocks	<ul style="list-style-type: none"> • Grating couplers • Inverted tapers • Spot size converters 	400 nm		Simulations <ul style="list-style-type: none"> • Component and circuit simulation • Technology files • Cross section 	150 nm		custom	<ul style="list-style-type: none"> ○ Modular ○ CMOS compatible ○ Scalable 				
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Commercial Offering

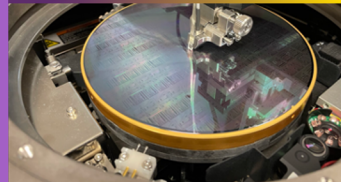
R&D and Prototyping

Open access, low barrier



Custom PIC Developments

High flexibility & competence

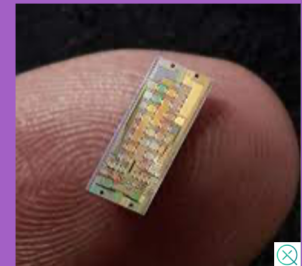


Manufacturing

Niche to high volumes



We deliver PICs



One base – many options:

SiN – The platform for monolithic & heterogeneous integration



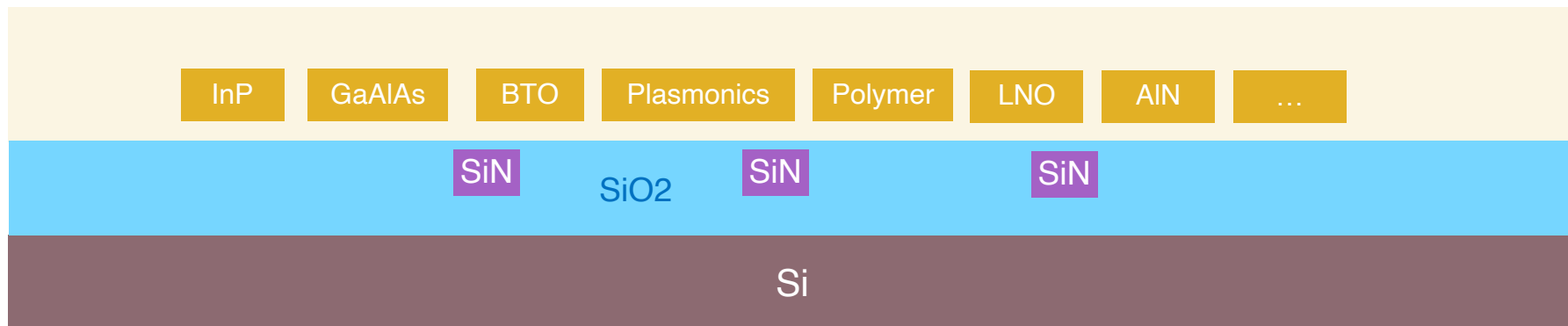
Use SiN as base platform for general circuitry

- Comprehensive PDK
- Standard I/Os
- Scalable to volume

Add materials as required by application

Focus on wafer level integration e.g.:

- Monolithic integration
- Wafer bonding
- Micro Transfer Printing



Monolithic Integration

Deposited or grown on the wafer

- Best cost option potential
- Performance trade-off
- Limited material choice
- Mature for same platform materials

Heterogeneous Integration

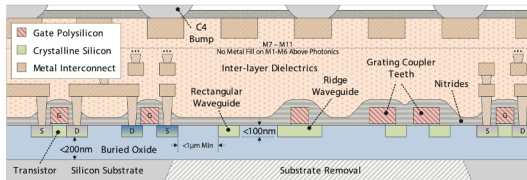
Transferred / bonded on the wafer

- High material integration flexibility
- Best material per application
- Low cost potential
- Emerging technology

Hybrid Integration

Assembled in the package

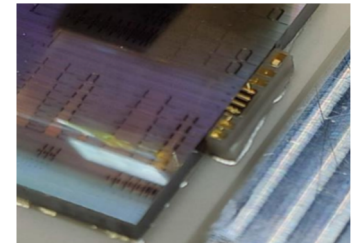
- High flexibility
- KGD integration
- Packaging complexity
- Costly in volumes



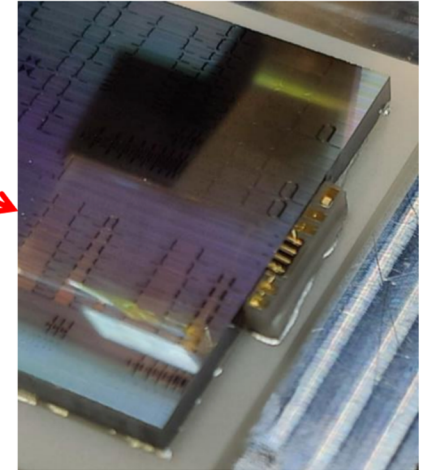
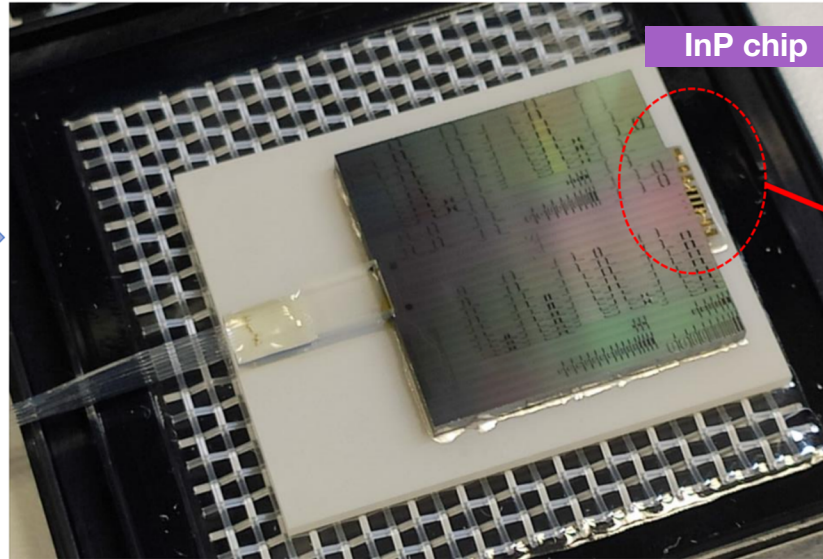
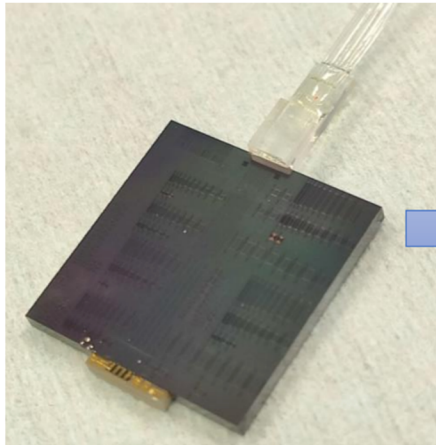
Sun et al., JSSC: 50, 893 (2016)



Source: EVG



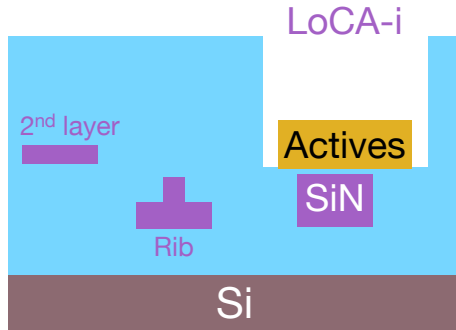
Hybrid Integration example InP Chip to passive SiN PIC



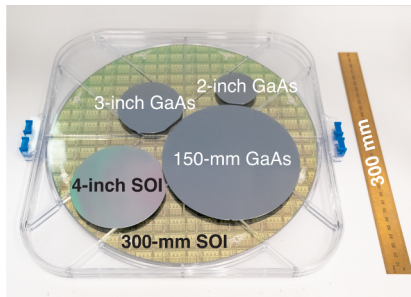
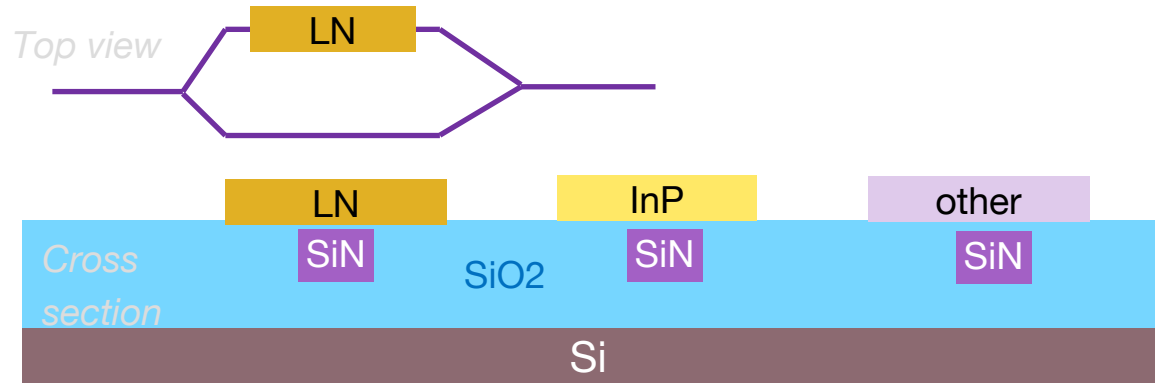
- SiN chip with FAU and SOA attached to it
- Assembly is glued on a ceramic carrier
- **Requires flat and smooth chip facets**

Heterogeneous Integration

Chip to Wafer

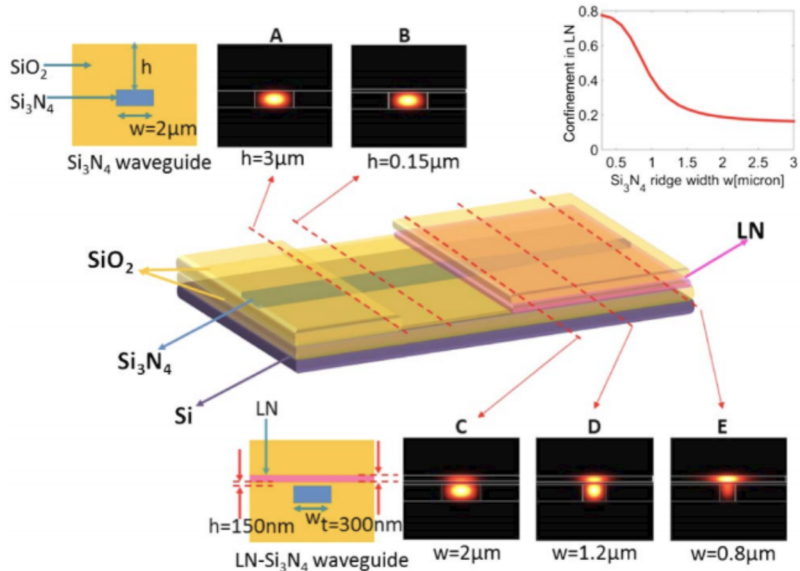


Wafer to Wafer



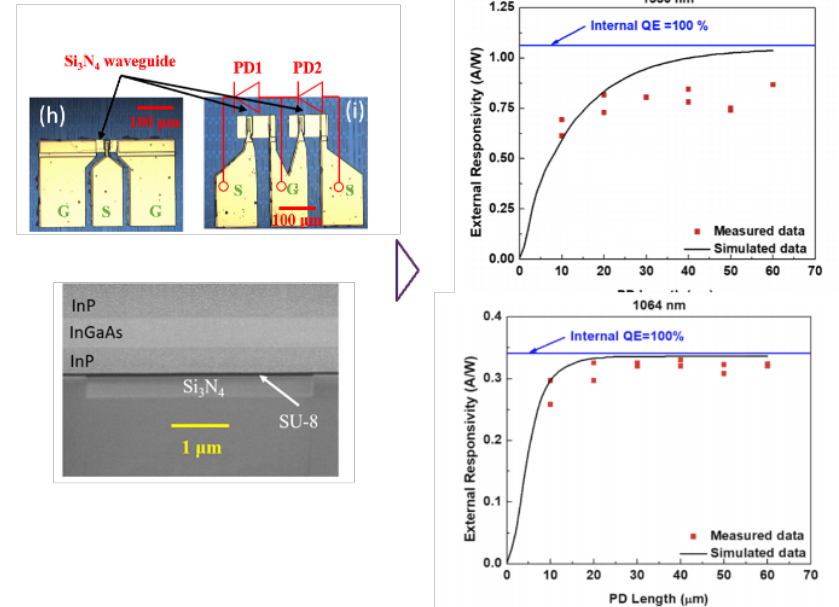
- Thermal budget, after material transfer, is reduced → increased propagation losses or new material
- Yield of combined stack is reduced ($\text{Yield}_{\text{SiN}} * \text{Yield}_{\text{active}} * \text{Yield}_{\text{integration}}$) → preference to test both active and SiN
- Wafer size not always available for W2W integration in photonics

LiNbO3



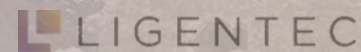
Heterogeneous integration of lithium niobate,
 Chang et al., Optics Letters (2017)

InGaAs Photodiodes



Heterogeneous photodiodes on SiN,
 Yu, Optics Express 28 (2020)

Thanks to all Ligentec Team



Join our PIC journey!

check out our openings at ligentec.com/careers
or send your CV to hr@ligentec.com

Moiry glacier 2021